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## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Hisashi Ohtani, et al

Art Unit : 1765

Serial No.: 08/690,747

Examiner : Robert Kunemund

Filed

: August 1, 1996

Confirmation No.: 1369

Title

: METHOD FOR MANUFACTURING SEMICONDUCTOR DEVICE

Commissioner for Patents Washington, D.C. 20231

## AMENDMENT

Sir:

In response to the Official Action dated June 26, 2002, Paper No. 29, in the above-referenced application, kindly amend the above-identified application as follows.

## In the Claims:

Please amend the claims as follows.

A method for manufacturing a semiconductor device comprising:

forming a semiconductor film comprising silicon over a substrate;

providing said semiconductor film with a crystallization promoting material;

## CERTIFICATE OF TRANSMISSION BY FACSIMILE

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